

# Organic Transistor (OFET) Materials Guide Book





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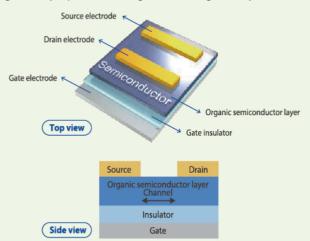
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#### **Organic Transistor (OFET) Materials**

Organic field-effect transistors (OFETs) are promising components for the next-generation electronic devices. In 1984, OFET research began with the first report of mobility in a merocyanine dye-based field-effect device by Kudo *et al.*<sup>1)</sup> Since high hole mobility (1.5 cm²/Vs), which comparable to that of amorphous silicon, was achieved using a pentacene-based OFET device in 1997,<sup>2)</sup> the possibility of a practical application of OFET's became realistic and the research field became quite popular worldwide. While silicon has performed well in devices, the inorganic nature of them prohibits flexible structures. As a result, OFETs have attracted much attention for their potential to be flexible, thin and light-weight, which could be applicable for foldable electronic circuits and implantable biometric sensors. <sup>3,4)</sup>

A noted potential application with OFET's involves their "printability". Printed electronics are an innovative technology for mass and low cost device productions, which could allow for the production of high density and large circuits on flexible substrates such as paper and plastic films. A fusion of "Printed electronics" and "Organic transistors" could offer especially promising technology by allowing for low cost and large scale manufacture of various functional devices. 5-7)

One of the functional parameters evaluated in organic semiconductor materials is mobility ( $\mu$ ), which indicates how fast the holes (p-type) or electrons (n-type) within the semiconducting layer move. A material that possesses high carrier mobility is required for producing high-speed circuits. OFET devices are a largely simple construction containing an organic semiconductor layer, an insulating layer, and source-drain-gate electrodes. These components allow for the evaluation of fundamental transistor parameters including mobility, operation voltage, and driving stability.



Due to the expanded  $\pi$ -conjugated system within organic semiconductor molecules, these often produce large intermolecular interactions inducing an improvement in the mobility within OFET devices.

In general, the expansion and extension of  $\pi$ -conjugation is an effective strategy in the molecular design of OFET molecules and polymers. As an example, Pentacene, which consists of 5 fused benzene rings, possesses superior electrical properties compared to that of Tetracene, which consists of 4 fused benzene rings. 8) However, a linear increase in the number of fused aromatic rings in a simple hydrocarbon system raises the Highest Occupied Molecular Orbital (HOMO), resulting in a critical decrease in the air-stability of the molecule and semiconductor materials. 8) This trade-off issue between the mobility and the air-stability of the materials has been a key problem to overcome. Given this context, in 2006 DPh-BTBT [D3526], a thienothiophene-fused organic compound, had been reported by Takimiya et al., as an innovative OFET material.9) DPh-BTBT features a deep HOMO level (-5.6 eV), which leads to remarkable air-stability during OFET device performance, and the HOMOs are well-distributed over the sulfur atoms of the thienothiophene moieties inducing good hole carrier transport. DPh-BTBT-based FET devise further achieved excellent electrical properties with a high hole mobility of 2.0 cm<sup>2</sup>/Vs. Followed by the innovation and molecular design of DPh-BTBT, Ph-BTBT-10, an smectic E (SmE) liquid crystalline material, was recently reported by Hanna et al., as a p-type material that bears an asymmetric structure in which the alkyl and the phenyl group are substituted on one side of the benzothienobenzothiophene (BTBT) moiety.<sup>10)</sup> Additionally, Ph-BTBT-10 can be handled in solution processing such the spin-coting method, and possesses both good heat-resistance and film-forming properties. The Ph-BTBT-10 spin-coated devise exhibited not only outstanding OFET performance with ultra-high mobility  $(\mu_{max} = 14.7 \text{ cm}^2/\text{Vs})$ , but also comparable to oxide semiconductors (IGZO) with remarkable air-stability.

One of the largest benefits of organic compounds for OFET's is their immense structural variety. This variety can be used to control the various properties they possess such as the electrical performance, stability, and processing characteristics through the chemical modification of the molecular units. Within the organic transistor research field, the possibilities for practical application has dramatically improved by introducing new concepts and various materials proposals, including the unique OFET materials and the parent molecules used to create them.

#### High Quality Organic Semiconductor Materials (For Organic Electronics)

TCI offers "High Quality Organic Semiconductor Materials (For Organic Electronics)" specialized for electrical performance such as OFET mobility\*. A material used in the active layer of an OFET device requires exceptionally high-purity to produce good OFET function. However, it is difficult to analytically (HPLC, GC, etc.) determine the purity at the ultra-high levels required for OFET function. To surmount this quality assurance challenge, we have begun in-house fabrication of OFET devices using our OFET materials. Once fabricated, we assess the functionality of the OFET as a quality assurance measure to confirm the electronic properties and device performance of the "High Quality Organic Semiconductor Materials (For Organic Electronics)". We constantly seek to improve our technology and skill in order to provide high-purity and quality materials our customers.

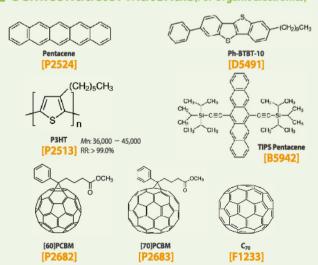
(\*The mobility refers to device evaluation measurements obtained within our facility under environment condition.)

#### Results of the device test are fed back to the synthesis and purification process





#### List of High Quality Organic Semiconductor Materials(For Organic Electronics)



			Specification			
Compound Product No.		Purity (%)	Mobility (cm²/Vs)	Si/SiO <sub>2</sub> Substrate Surface Condition		
Pentacene	P2524	> 99.999	> 0.35	Bare		
Ph-BTBT-10	D5491	> 99.5	> 10.0	ODTS		
P3HT	P2513	Pd: < 100ppm	> 0.10	OTS		
TIPS Pentacene	B5942	>99.0	> 0.10	HMDS		
C <sub>70</sub>	F1233	>99.0	> 0.30	HMDS		
[60]PCBM	P2682	>99.5	> 0.020	HMDS		
[70]PCBM	P2683	>99.0	> 0.015	HMDS		

#### 1. An Example of OFET Evaluation 1: Typical p-type Material "Pentacene"

#### **Pentacene**

[P2524]

(99.999%, trace metals basis) (purified by sublimation)

Pentacene, a simple polyaromatichydrocarbon, has been studied for its fundamental properties and applications in organic electronic research.<sup>11,12)</sup> In particular, many research studies have been conducted to evaluate its potential as a carrier transporter within OFET devices.<sup>2,13)</sup> TCI provides two subliminally purified pentacene reagents: P2524 and P0030. P2524 (99.999% trace metal basis) is our high-quality grade reagent, which has additional specifications for its OFET mobility: [> 0.35 cm²/Vs (bare Si/SiO₂)]. We inspect P2524 through the OFET evaluation process in every product lot. Only lots that pass this functional test are packed and shipped as "High Quality Organic Semiconductor Materials (For Organic Electronics)".

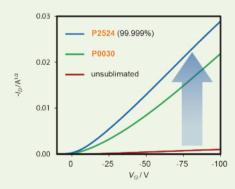


Figure 1. Transfer curves of various grades of pentacene.

Table 1. OFET characteristics of the pentacenes.

Product No.	Sample grade	Substrate	Mobility (cm <sup>2</sup> /Vs)	$V_{th}$
-	Pentacene (non-sublimation)	Si/SiO <sub>2</sub> (bare)	5.3 × 10 <sup>-4</sup>	-13
P0030	Pentacene (purified by sublimation)	Si/SiO <sub>2</sub> (bare)	0.29	-22
P2524	Pentacene (99.999%, trace metals basis) (purified by sublimation)	Si/SiO <sub>2</sub> (bare)	0.39	-10

The performances of the pentacene-based OFET devices are summarized in Table 1 and Figure 1. These devices were fabricated via vacuum deposition method on bare Si/SiO<sub>2</sub> substrate without Self-Assembled Monolayer (SAM) treatment, the characteristics of which were measured under nitrogen conditions. Our sublimed pentacene [P2524] showed a large increase OFET performance compared to that of the non-sublimed pentacene. As a result, P2524 (99.999% trace metal basis) showed an excellent OFET performance with the highest hole mobility of 0.39 cm<sup>2</sup>/Vs. In comparison to other companies' sublimed pentacene samples, P2524 (99.999% trace metal basis) possesses the highest drain current and the best OFET potential (Figure 2 and Table 2).

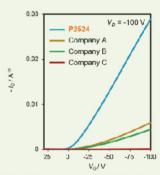


Figure 2. Transfer curves of OFET devices using several companies' pentacene.

Table 2. OFET characteristics of the pentacenes.

	Substrate	Mobility (cm²/Vs)	V <sub>th</sub>
P2524	Si/SiO <sub>2</sub> (bare)	0.39	-10
Company A (sublimed)	Si/SiO <sub>2</sub> (bare)	0.002	-25
Company B (sublimed)	Si/SiO <sub>2</sub> (bare)	0.001	-25
Company C (sublimed)	Si/SiO <sub>2</sub> (bare)	$5.0 \times 10^{-6}$	-23

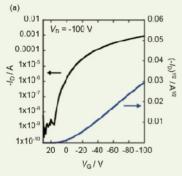
#### 1-a. Optimization of pentacene-based OFET devices

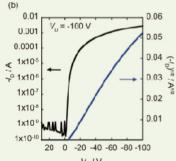
We have examined and optimized the functional preformance of pentacene-based OFET devices via substrate surface modification. The field-effect mobility of pentacene was measured using top-contact thin-film field-effect transistors geometry (Figure 3). The thin film of pentacene [P2524] as the active layer (60 nm) was vacuum-deposited onto Si/SiO<sub>2</sub> substrate (bare) or *n*-Octyltrichlorosilane (OTS) [O0168] -treated Si/SiO<sub>2</sub> substrate at room temperature (*T*<sub>Sub</sub> = RT). The drain and source electrodes (40 nm) were then prepared by gold evaporation through a shadow mask on top of the pentacene film; the drain-source channel length (*L*) and width (*w*) were 50 µm and 1.5 mm, respectively. The characteristics of the OFET devices were measured under nitrogen conditions.

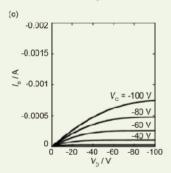
The performances of the OFET devices are summarized in Table 3 and figure 4. All pentacene -based devices exhibited pure typical p-channel field-effect transistor (FET) characteristics. The FET performance were significantly improved by the SAM treatment; the OTS-treated device demonstrated the highest performance with a hole carrier mobility of  $1.52 \, \mathrm{cm^2/Vs}$  and an on/off ratio of  $1.5 \times 10^7$  (Figure 4).

Figure 3. Illustration for the device structure of pentacene-based OFET device.









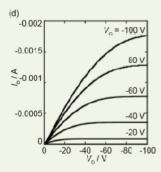


Figure 4. Typical OFET characteristics of top-contact devices fabricated using pentacene [P2524].

(a, c) bare. (b, d) OTS-treated substrate.

(a, b) Transfer curves in the saturated region.

(c, d) Output curves at different gate voltages.

Table 3. OFET characteristics of P2524-based devices.

Compound	SAM	Tsub (°C)	Mobility (cm²/Vs)	V <sub>th</sub>	on/off
Pentacene	bare	RT	0.35 ~ 0.37	-5.3	3.9 X 10⁵
[P2524]	OTS[00168]	RT	1.50 ~ 1.52	-5.7	1.5 X 10 <sup>7</sup>

#### 1-b. AFM images and XRD analysis

To clarify the pentacene thin film morphology and conformation, atomic force microscope (AFM) and X-ray diffraction (XRD) measurement were carried out (Figure 5). Regardless of either bare or OTS-treated substrate, highly regular terrace structures were observed (Figure 5a). In addition, XRD measurements of the pentacene films showed a series of peaks assignable to (00h) reflections; and the diffraction peak at  $2\theta = 5.72^{\circ}$  corresponds to a *d*-spacing of 15.5 Å (Figure 5b). These results demonstrated that the pentacene molecules stood nearly perpendicular to the substrate (thin-film-phase) in the film form. <sup>12, 13)</sup>

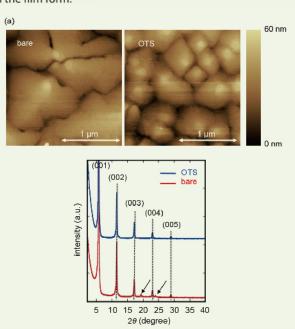


Figure 5. AFM images(a). and XRD analysis(b) of pentacene filims.

In the bare device (without SAM), two weak peaks assignable to face-on orientation were observed (Figure 5b, black arrow), which would create the disadvantage of carrier passes parallel to the substrate (Figure 6a). In contrast, such peaks were not observed in the pentacene film on the OTS-treated substrate (Figure 6b). It is one reason why the mobility was higher in the OTS-treated OFET device.

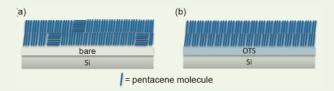


Figure 6. Orientation images of pentacene thin film form.

#### 2. An Ultra-high Performance p-type Semiconductor Material "Ph-BTBT-10"

Ph-BTBT-10 (= 2-Decyl-7-phenyl[1]benzothieno[3,2-b][1]benzothiophene) [D5491]

Ph-BTBT-10, an SmE liquid crystalline material, has been recently reported by Hanna *et al.*, as a p-type material which possesses excellent transport properties. Ph-BTBT-10 exhibits ultra-high mobility ( $\mu_{max} = 14.7 \text{ cm}^2/\text{Vs}$ ) comparable to oxide semiconductors (IGZO), and remarkable air stability. TCI has recently commercialized Ph-BTBT-10 as an ultra-high mobility and air stability p-type OFET material, and has begun evaluation via the fabrication and performance measurement of Ph-BTBT-10-based OFET devices using vacuum deposition methods in our laboratories. The devise showed a hole carrier mobility up to 14.0 cm²/Vs. Please see below for details.

#### 2-a. Fabrication and evaluation of Ph-BTBT-10-based OFET device

The field-effect mobility of Ph-BTBT-10 was measured using top-contact thin-film field-effect transistors geometry (Figure 7). The thin film of Ph-BTBT-10 as the active layer (40 nm) was vacuum-deposited onto  $Si/SiO_2$  substrate (bare) or Octadecyltrichlorosilane (ODTS) [O0079]-treated  $Si/SiO_2$  substrate while heating the substrate. The drain and source electrodes (40 nm) were then prepared by gold evaporation through a shadow mask on top of the Ph-BTBT-10 film; the drain-source channel length (L) and width (w) are 50  $\mu$ m and 1.5 mm, respectively. After deposition, these devices were thermal annealed at  $T_{Sub} = 120$  °C for 5 min under ambient conditions, and the characteristics of the OFET devices were measured.

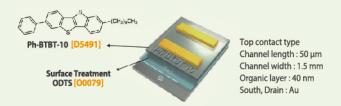


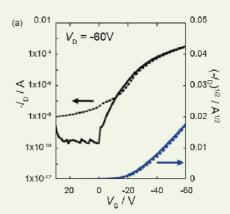
Figure 7. Illustration for the device structure of Ph-BTBT-10-based OFET.

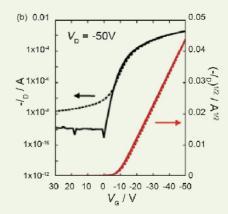
The performances of the OFET devices are summarized in Table 4 and Figure 8. All Ph-BTBT-10-based devices exhibited pure typical p-channel field-effect transistor (FET) characteristics. The FET mobilities were quite dependent on the thermal annealing treatment regardless of the self-assemble-monolayer (SAM)

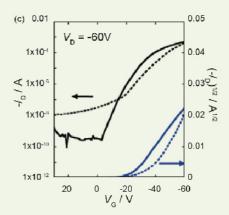
(Figure 8). This would be attributed to the phase transition from a monolayer to a bilayer crystal structure in the thin-film form. <sup>10)</sup> The device fabricated on bare substrate demonstrated good performance with a hole carrier mobility of 4.86 cm²/Vs and threshold voltage (*V*th) of -8 V. Moreover, although *V*th increased, the ODTS-treated devise showed the highest transport performance with a hole carrier mobility of 14.0 cm²/Vs.

Table 4. OFET characteristics of the Ph-BTBT-10-based devices

Compound	SAM	Annealing Temp.	Mobility (cm²/Vs)	V <sub>th</sub>
Ph-BTBT-10	bare	w/o 120	0.87 ~ 0.91 4.24 ~ 4.86	-24 -8
[D5491]	ODTS [00079]	w/o 120	1.40 ~ 1.42 10.3 ~ 14.0	-23 -22







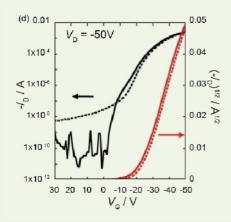
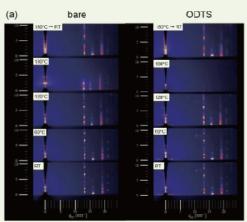


Figure 8. Transfer curves of the Ph-BTBT-10-based OFET devices.
(a) w/o annealing (bare) (b) annealing 120°C, 5min (bare)
(c) w/o annealing (ODTS) (d) annealing 120°C, 5min (ODTS)

#### 2-b. 2D-GIXD Analysis



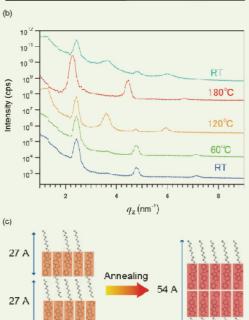


Figure 9. (a) 2D-GIXD analysis (Thermal in situ mesurement), (b) 2D-GIXD analysis (Out-of-plane, bare substrate), (c) Phase transition images of Ph-BTBT-10

The crystal structures of Ph-BTBT-10 thin films were analyzed by 2D-GIXD using synchrotron radiation. Figure 9 (a) and (b) display the thermal in situ 2D-GIXD data at different temperatures. The Ph-BTBT-10 films at RT and 60°C showed a similar series of peaks assignable to a monolayer structure with a d-spacing of 27 Å. When the substrate temperature was increased to 120°C, the diffraction peaks clearly changed, which suggested a transformation from a monolayer structure (d = 27 Å) into a bilayer structure with a d-spacing of 54 Å as shown in Figure 9 (c). Since the phase transition temperature to the SmE mesophase is 144°C, 10) a series of peaks assignable to SmE were observed when heated to 180°C. In addition, a mixed layer of monolayer and bilayer structures appeared when the Ph-BTBT-10 thin film was rapidly cooled from 180°C to RT. These results indicate that under these conditions the cooling speed might be a significant factor in forming a well-uniformed crystalline thin film structure. Based on these results, Ph-BTBT-10 can be handled through vacuum deposition method, and the phase transition from the monolayer to the bilayer structure can occur in the same way in which it occurs for solution processed Ph-BTBT-10 thin films.<sup>10)</sup> Finally, we demonstrated top-ranked FET performances via vacuum deposition process using our in-house equipment.

#### 3. Performance Evaluation of Highly Regioregular "P3HT"

#### P3HT(= Poly(3-hexylthiophene-2,5-diyl) (regioregular) [P2513]

TCl's P3HT (Poly(3-hexylthiophene-2,5-diyl)) [P2513] features a very high regioregularity (RR > 99%), a narrow molecular weight distribution (Mn = 36k  $\sim$  45k), and a low metal content ratio (Pd < 100 ppm) in order to provide high quality solution-processed organic materials for organic electronics. The synthesis was conducted via the direct aryration polymerization (DArP) method in collaboration with Prof. Fumiyuki Ozawa at Institute for Chemical Research, Kyoto University. 14, 15)

We fabricated organic thin-film transistor (OFET) devices to validate and demonstrate hole transport properties of P3HTs. By comparing OFET characteristics of six P3HT samples including P2513, we revealed a correlation between OFET performances and (1) molecular weights and (2) regioregularities of P3HTs. As the result, the P2513 devise showed the highest hole mobility, among the other P3HT devices. This suggested that the carrier transport property of P3HT was improved by both the regioregularity and the molecular weight of polymer parameters. In particular, the regioregularity could be considered the most significant factor for enhancing the electrical properties of P3HT in an OFET device.

#### 3-a. Fabrication and Evaluation of P3HT-based OFET devices

The hole mobility of P2513 was measured using top-contact OFET geometry (Figure 10). The P3HT [P2513] was dissolved in chloroform:trichlorobenzene at a concentration of 10 mg/ml. The solution of P2513 was spin-coated (1500 RPM) onto n-Octyltrichlorosilane (OTS) [O0168]-treated Si/SiO<sub>2</sub> substrate in a nitrogen glove box, then thermally annealed for 30 min. A gold layer with 40 nm thickness was deposited in vacuum chamber to serve as drain and source electrodes through a shadow mask on top of the P2513 film; the drain-source channel length (L) and width (W) are 50  $\mu$ m and 1.5 mm, respectively. The characteristics of the OFET devices were measured under nitrogen conditions. The other five P3HTs were also evaluated under the same protocol.

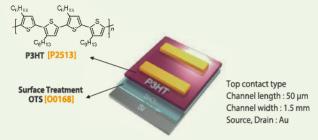


Figure 10. Illustration for the device structure of P3HT-based OFET.

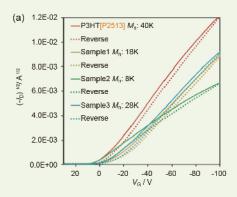
#### 3-b. A correlation between the hole transport mobility and the molecular weight<sup>18)</sup>

The device performances of P2513 (high molecular weight Mn: 40K) and the other three P3HT samples having low molecular weights (Mn: 8K~28K), are summarized in Figure 11 and Table 5. Samples 1 and 2 were synthesized via the same DArP method same as with P2513.

The OFET performances of P3HT-based devices were improved by increasing the molecular weights of P3HT. In the case of P2513, the device achieved the highest transport performance with a hole mobility of 0.1 cm<sup>2</sup>/Vs and an on/off ratio of 9×10<sup>4</sup>. The high molecular weight could enhance a crystallinity of P3HT in the film form, that could be a reason why P2513 possesses the excellent performances of OFET. The molecular weight of P2513 was set 30K ~ 45K as a specification.

Table 5. Properties of P3HTs and mobility of OFET devices.

	RR (%)	M <sub>n</sub>	Mobility (X 10 <sup>-2</sup> cm <sup>2</sup> /Vs)
P2513	99	40K	10.5±0.4
Sample 1	99	18K	5.9±0.3
Sample 2	99	8K	3.0±0.4
Sample 3	98	28K	6.5±0.7
Sample 4	91	39K	1.2±0.1
Sample 5	93	-	1.7±0.3



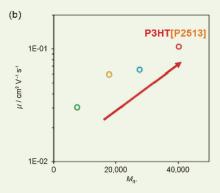
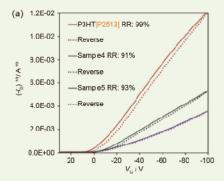


Figure 11. (a) Transfer curves of P3HT-based devices differ from molecular weight of P3HT, (b) A correlation between the hole transport mobility and the molecular weight.

#### 3-c. A correlation between the hole transport mobility and the regioregularity<sup>19)</sup>

The device performances of P2513 (the high regioregularity >99%) and the other two P3HT samples having low regioregularities (91, 93%) are summarized in Figure 12 and Table 5. Samples 4 and 5 indicate other companies' P3HT. The OFET performances of P3HT-based devices were drastically improved with increasing the regioregularities within P3HTs. While sample 4 (RR: 91%, Mn: 39K) displayed a high molecular weight as P2513 (Mn: 40K), the hole transport mobility of the sample 4-based device was lower than that of the sample 2 (RR: 99%, Mn: 8K) -based device. From these results, the OFET performances of P3HT could be enhanced by the regioregularity rather than the molecular weight of P3HT.



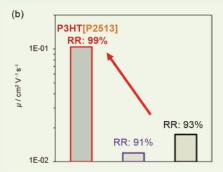
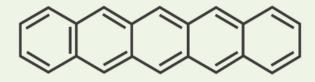


Figure 12. (A) Transfer curves of P3HT-based devices differ from regioregularity of P3HT, (b) A correlation between the hole transport mobility and the regioregularity.

#### References

- K. Kudo, M. Yamashinaand, T. Moriizumi, *Jpn. J. Appl. Phys.* 1984, 23, 130.
- 2) Y. Y. Lin, D. J. Gundlach, S. F. Nelson and T. N. Jackson, *IEEE Trans. Electron Devices* **1997**, *44*, 1325.
- M. Kaltenbrunner, T. Sekitani, J. Reeder, T. Yokota, K. Kuribara, T. Tokuhara, M.Drack, R. Schwödiauer, I. Graz, S. Bauer-Gogonea, S. Bauer, T. Someya, *Nature* 2013, 499, 458.
- 4) B. Chu, W. Burnett, JW. Chung, Z. Bao, Nature 2017, 355, 328.
- A. C. Arias, J. D. MacKenzie, I. McCulloch, J. Rivnay, A. Salleo, Chem. Rev. 2010, 110, 3.
- B. Kang, W. H. Lee, K. Cho, ACS Appl. Mater. Interfaces 2013, 5, 2302.
- 7) K. Fukuda, T. Someya, Adv. Mater. 2017, 29, 1602736.
- 8) J. G. Mei, Y. Diao, A. L. Appleton, L. Fang, Z. N. Bao, *J. Am. Chem. Soc.* **2013**, *135*, 6724.
- K. Takimiya, H. Ebata, K. Sakamoto, T. Izawa, T. Otsubo, Y. Kunugi, J. Am. Chem. Soc. 2006, 128, 12604.
- 10) H. lino, T. Usui, J.-l. Hanna, Nat. Commun. 2015, 6, 6828.
- 11) R. Ruiz, D. Choudhary, B. Nickel, T. Toccoli, K.-C. Chang, A. C. Mayer, P. Clancy, J. M. Blakely, R. L. Headrick, S. lannotta, G. G. Malliaras, Chem. Mater. 2004, 16, 4497.
- B. Nickel, M. Fiebig, S. Schiefer, M. Göllner, M. Huth, C. Erlen, P. Lugli, Phys. Stat. Sol. A 2008, 205, 526
- 13) M. Kitamura, Y. Arakawa, J. Phys.: Condens. Matter. **2008**, 20, 184011
- 14) Q. Wang, R. Takita, Y. Kikuzaki, F. Ozawa, J. Am. Chem. Soc. **2010**, *132*, 11420.
- J.-R. Pouliot, M. Wakioka, F. Ozawa, Y. Li, M. Leclerc, Macromol. Chem. Phys. 2016, 217, 1493.
- 16) R. Zhang, B. Li, M. C. Iovu, M. Jeffries-EL, G. Sauvé, J.Cooper, S. Jia, S. Tristram-Nagle, D. M. Smilgies, D. N. Lambeth, R. D. McCullough, T. Kowalewski, J. Am. Chem. Soc. 2006, 128, 3480.
- 17) H. Sirringhaus, P. J. Brown, R. H. Friend, M. M. Nielsen, K. Bechgaard, B. M. W. Langeveld-Voss, A. J. H. Spiering, R. A. J. Janssen, E. W. Meijer, P. Herwig, D. M.de Leeuw, *Nature* 1999, 401, 685.
- J.-F. Chang, B. Sun, D. W. Breiby, M. M. Nielsen, T. I. Sölling, M. Giles, I. McCulloch, H. Sirringhaus, Chem. Mater. 2004, 16. 4772.
- L. A. Majewski, J. W. Kingsley, C. Balocco, A. M. Songa, *Appl. Phys. Lett.* **2006**, *88*, 222108.

#### p-Type Organic Semiconductor High-purity and High-performance Pentacene

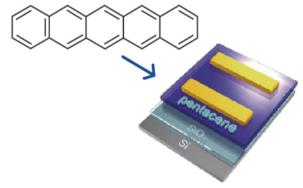


Pentacene (99.999%, trace metals basis) (purified by sublimation) [for organic electronics] 100mg / 1g

[P2524]

- Advantages · Electronic material grade [High-purity, low metal (< 10 ppm)]
  - · Extremely purified by sublimation
  - Ensures semiconductor performance by OFET devices [Specification: hole mobility > 0.35 cm<sup>2</sup>/Vs (bare Si/SiO<sub>2</sub> substrate)]

#### **Comparison of transistor performance**



**Top-contact device** [Si<sup>n+</sup> / SiO<sub>2</sub> / pentacene / Au]

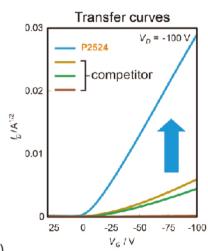


Table 1. OFET characteristics (using in-house equipment)

	Substrate	Hole Mobility (cm²/Vs)	Threshold voltage (V)
P2524		0.39	-10
Competitor A (sublimed)	Si/SiO₂ (bare)	0.002	-25
Competitor B (sublimed)	(bare)	0.001	-25
Competitor C (sublimed)		5.0 × 10 <sup>-6</sup>	-23

#### **Applications**

The FET performance was significantly improved by surface modification with Self-Assembled Monolayer (SAM)(OTS: n-octyltrichlorosilane [O0168]); the OTS-treated device with the pentacene [P2524] demonstrated very high FET performance (Figure 1 and Table 2).

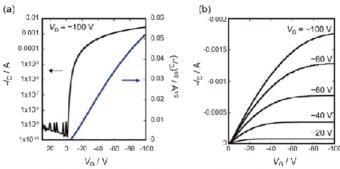


Figure 1. (a) transfer curves (b) output curves

Table 2. OFET characteristics (using in-house equipment)

	SAM	Tsub (°C)	Hole Mobility (cm² / Vs)	<i>V</i> тн (V)	on/off ratio
Pentacene [P2524]	OTS [O0168]	RT	1.50 - 1.52	-5.7	1.5 × 10 <sup>7</sup>

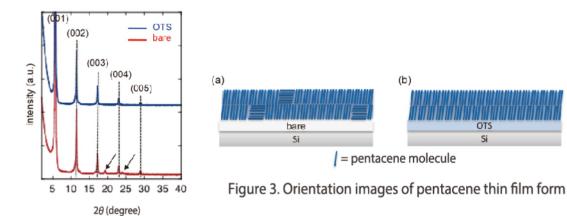


Figure 2. XRD analysis

In the bare device (without SAM), two weak peaks assignable to face-on orientation were observed (Figure 2, black arrow). This may cause a strong barrier to reduce carrier mobility (Figure 3a). On the other hand, the pentacene film on the OTS-treated substrate did not show such peaks (Figure 2). These results indicate that the OTS-treated device involves an excellent thin-film drastically enhancing the FET performance (Figure 3b).

A part of X-ray diffraction (XRD: Smart Lab) was conducted at Advanced Characterization Nanotechnology Platform of the University of Tokyo, supported by "Nanotechnology Platform" of the Ministry of Education, Culture, Sports, Science and Technology (MEXT), Japan.

Related Product *n*-Octyltrichlorosilane (= OTS)

25g / 250g [**O0168**]

## Stable p-Type Organic Semiconductor Dimethylanthradithiophene (DMADT)

**anti-DMADT** (purified by sublimation) 100mg

[D4617]

**syn-DMADT** (purified by sublimation) 100mg

[D4618]

#### (Advantages)

- More stable toward oxidation because of its lower HOMO-level compared with pentacene
- Applicable to device-fabrication using the single isomer because high pure anti-DMADT and syn-DMADT are free from isomer contamination

#### **FET Characteristics**

	Mobility μ (cm²/Vs)	On/Off ratio	Threshold (V)	
anti-DMADT	0.41	106	-19	
syn-DMADT	0.084	105	-25	

Reference M. Mamada, T. Minamiki, H. Katagiri, S. Tokito, *Org. Lett.* **2012**, *14*, 4062. DOI: https://doi.org/10.1021/ol301626u

#### **Related Products**

**Pentacene** (purified by sublimation) 100mg / 1g [P0030] **Pentacene** (99.999%, trace metals basis) (purified by sublimation) 100mg / 1g [P2524]

## High-Mobility / High-Solubility p-Type Organic Semiconductor Ph-BTBT-n Series

 Ph-BTBT-12
 100mg / 250mg / 1g [D5910]

 Ph-BTBT-10
 100mg / 250mg / 1g [D5491]

 Ph-BTBT-8
 100mg / 250mg / 1g [O0576]

 Ph-BTBT-6
 100mg / 250mg / 1g [H1769]

 Ph-BTBT-4
 100mg / 250mg / 1g [B6248]

#### **Advantages**

- "Mobility" and "Solubility" highly depend on the alkyl chain length
- · Material choice according to user's purpose and operating environment
- Applicable to both dry and wet processes

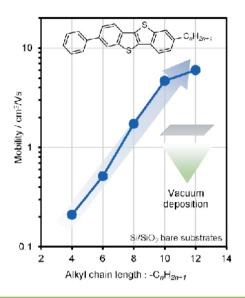
#### A correlation between "alkyl chain length" and "mobility / solubility" Ph-BTBT-4 Ph-BTBT-6 Ph-BTBT-8 Ph-BTBT-10 Ph-BTBT-12 [B6248] [H1769] [00576] [D5491] [D5910] **Shorter** the alkyl chain **Longer** the alkyl chain **Higher** the solubility **Higher** the mobility Solubility 4 10 12 Alkyl chain length: $-C_nH_{2n+1}$

The products are assessed for its electrical performance (mobility) as a quality assurance through our in-house OFET device evaluation.

#### Assessment of vacuum deposited transistor devices (in-house data)

Compound

#### A comparison of mobilities : Ph-BTBT-n series



#### A comparison of OFET performance: Typical transistor materials

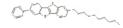
Ph-BTBT-10 C8-BTBT DNTT

	Mobility / cm²/Vs				4.2	0.7
	6.0E-02 <sub>1</sub>	_				
	5.0E-02 -		ansfer irves	=	Ph-BTBT-1 C8-BTBT DNTT	
	4.0E-02					
7 / 4 172	3.0E-02 -		V			
	2.0E-02 -	,	Vacuum deposition		17	
	1.0E-02 -	V.	<sub>i</sub> = -50 V		ODTS-	treated
	0.0E+00				Si/SiO <sub>2</sub> s	ubstrates
			0	Vo	-25 ; / V	-50

#### Fabrication and evaluation of transistor devices by wet processes (previous works)

#### Spin-coating method<sup>1)</sup>

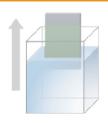




#### Ph-BTBT-10 [D5491]

- Hot spin-coating deposition
- Polycrystalline thin-film
- Bottom-contact type
- · Mobility: 11cm<sup>2</sup>/Vs

#### Dip-coating method<sup>2)</sup>





#### Ph-BTBT-10 [D5491]

- Hot dip-coating and high speed deposition
- Polycrystalline thin-film (large area)
- Bottom-contact type
- · Mobility: 4 cm<sup>2</sup>/Vs

#### References:

- 1) H. lino, T. Usui, J. Hanna, Nat. Commun. 2015, 6, 6828.
- 2) H. Wu, H. lino, J. Hanna, ACS Appl. Mater. Interfaces 2020, 12, 29497–29504.
- 3) S. Arai, S. Inoue, T. Hamai, R. Kumai, T. Hasegawa, Adv. Mater. 2018, 30, 1707256.

#### Blade-coating method<sup>3)</sup>



Ph-BTBT-6 [H1769]

Ph-BTBT-10 [D5491]

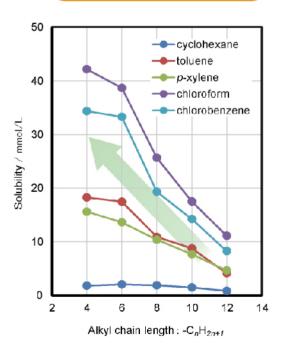
- Blade-coating deposition
- Control over the number of deposited layers by mixing two materials
- Single crystalline thin-film (large area)
- Top-contact type
- · Mobility: 6 cm<sup>2</sup>/Vs

#### **Physical property data**

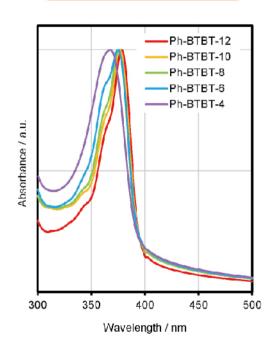
compound	mobility <sup>a</sup> / cm²/Vs		solubility <sup>b</sup> / mmol/L		absorption spectrachymm		mp <sup>4)</sup>
	bare substrate (ODTS substrate)	toluene	chloroform	absorption maximaum	absorption edge	temp. <sup>4)</sup> /°C	/∘⊂
Ph-BTBT-12	6.0	4.1	11.1	378	396	140	218
Ph-BTBT-10	4.7 (11.0)	8.8	17.5	377	395	147	225
Ph-BTBT-8	1.7	10.9	25.7	376	394	148	231
Ph-BTBT-6	0.5	17.5	38.7	375	394	159	237
Ph-BTBT-4	0.2	18.3	42.2	368	393	-	245

<sup>&</sup>lt;sup>a</sup>Top-contact transistor devices fabricated by vacuum deposition method (in-house). <sup>b</sup>Data obtained at room temperature. <sup>c</sup>In vacuum deposited thin-films.

#### Solubility in organic solvents (in-house data)



#### UV-vis spectra of vacuum deposited thin-films (in-house data)



#### **References:**

4) S. Inoue, H. Minemawari, J. Tsutsumi, M. Chikamatsu, T. Yamada, S. Horiuchi, M. Tanaka, R. Kumai, M. Yoneya, T. Hasegawa, *Chem. Mater.* **2015**, *27*, 3809–3812.

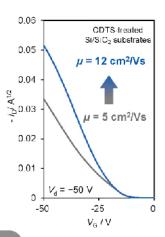
#### **Quality assurance by FET mobility**

#### An effect of low amount of impurities on electrical properties

- Both purities are over 99.5%.
- Clear difference of FET performance
- FET mobility is set as a specification. TCI offers real "practical materials".



Evaluation of vacuum deposited OFET devices:
Ph-BTBT-10 sample



Results of the device test are fed back to the synthesis and purification processes



Each product has a product specification as below.

Ph-BTBT-12[D5910] hole mobility of > 5.0 cm<sup>2</sup>/Vs (vacuum deposition method, Si/SiO₂ bare substrate)

Ph-BTBT-10[D5491] hole mobility of > 10.0 cm<sup>2</sup>/Vs (vacuum deposition method, ODTS-treated Si/SiO<sub>2</sub> substrate)

**Ph-BTBT-8** [O0576] hole mobility of > 1.2 cm<sup>2</sup>/Vs (vacuum deposition method, Si/SiO<sub>2</sub> bare substrate)

Ph-BTBT-6 [H1769] hole mobility of > 0.4 cm<sup>2</sup>/Vs (vacuum deposition method, Si/SiO<sub>2</sub> bare substrate)

Ph-BTBT-4 [B6248] hole mobility of > 0.1 cm<sup>2</sup>/Vs (vacuum deposition method, Si/SiO₂ bare substrate)

#### **Related Products**

**High-performance organic semiconductors** 

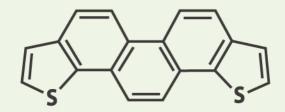
**S-DNTT-10** [for organic electronics] 100mg / 250mg [D5796] **TU-1** [for organic electronics] 100mg / 250mg [T3922]

**TU-3** [for organic electronics] 100mg / 250mg [T3924]

Surface treatment agent

Octadecyltrichlorosilane (>99.0%) (= ODTS) 1g [T3815]

## p-Type Semiconducting Picene Derivative Phenanthrodithiophene



Phenanthro[1,2-b:8,7-b']dithiophene

[P2383]

#### Advantages

- The field-effect mobility is as high as 10<sup>-1</sup> cm<sup>2</sup>/Vs when used in the thin films of the field-effect transistor (FET).
- Applicable to the synthesis of semiconducting polymers by using stannylated or brominated P2383.

#### **Application**

donor-acceptor (D-A)-type semiconducting polymer

#### References

H. Mori, M. Suetsugu, S. Nishinaga, N. Chang, H. Nonobe, Y. Okuda, Y. Nishihara, *J. Polym. Sci., Part A: Polym. Chem.* **2015**, *53*, 709. Y. Nishihara, M. Kinoshita, K. Hyodo, Y. Okuda, R. Eguchi, H. Goto, S. Hamao, Y. Takabayashi, Y. Kubozono, *RSC Adv.* **2013**, *3*, 19341. Y. Nishihara, ADEKA CORP., Jpn. Kokai Tokkyo Koho 2014-240483, **2014**.

#### **Organic Semiconducting Polymer Highly Regioregular P3HT**

P3HT (regioregular) [for organic electronics]

100mg / 500mg

[P2513]

- Advantages · High regioregularity (RR) >99.0%
  - Number average molecular weight : Mn = 27,000 45,000
  - Electronic material grade: High purity, low metal (Pd <100 ppm)</li>
  - · Highly soluble, excellent to film

#### Synthesis of P3HT by direct arylation polymerization (DArP) and physical properties<sup>1,2)</sup>

H 
$$\sim$$
 S  $\sim$  CCH<sub>2</sub>)<sub>5</sub>CH<sub>3</sub>  $\sim$  DArP  $\sim$  CCH<sub>2</sub>)<sub>5</sub>CH<sub>3</sub>  $\sim$  N RR >99.0%

[P2513] *DArP* = *Direct Arylation Polymerization* 

#### The data is extracted from Ref. 2)

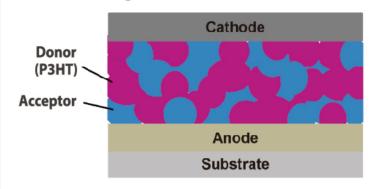
Method	M <sub>n</sub> (PDI)	RR / %	<i>T</i> <sub>m</sub> (°C)	μ <sub>max</sub> (cm²/V·s)
DArP	33,000 (1.8)	99.5	237	0.19
Rieke	25,000 (1.3)	95.5	224	0.02
GRIM	88,000 (1.5)	98.0	234	0.11

- 1) Q. Wang, R. Takita, Y. Kikuzaki, F. Ozawa, J. Am. Chem. Soc. 2010, 132, 11420.
- 2) J.-R. Pouliot, M. Wakioka, F. Ozawa, Y. Li, M. Leclerc, Macromol. Chem. Phys. 2016, 217, 1493.

This product was commercialized under instruction by Prof. Fumiyuki Ozawa.

#### **Applications**

#### **Organic Photovoltaics (OPV)**<sup>1)</sup>



#### P3HT: Donor material

Usable for a solution processable OPV device Fabricates a bulk heterojunction (BHJ) with a highly soluble donor and acceptor

#### Perovskite Solar Cell (PSC)<sup>2)</sup>

Au
P3HT (HTM layer)
Perovskite
TiO <sub>2</sub> + Perovskite
TiO <sub>2</sub>
FTO

#### P3HT: Hole transport material (HTM)

Usable for a solution processable PSC device Realizes high power conversion efficiency

#### **Organic Transistor (OFET)**<sup>3)</sup>



#### P3HT: p-Type semiconductor

Usable for a solution processable OFET device

#### References

- 1) OPV:
  - a) E. L. Lim, C. C. Yap, M. A. M. Teridi, C. H. Teh, A. R. M. Yuso, M. H. H. Jumali, *Org. Electron.* **2016**, *36*, 12. b) A. Marrocchi, D. Lanari, A. Facchetti, L. Vaccaro, *Energy Environ. Sci.* **2012**, *5*, 8457.
- 2) PSC: L. Calió, S. Kazim, M. Grätzel, S. Ahmad, Angew. Chem. Int. Ed. 2016, 55, 14522.
- 3) OFET: H. Sirringhaus, Adv. Mater. 2014, 26, 1319.

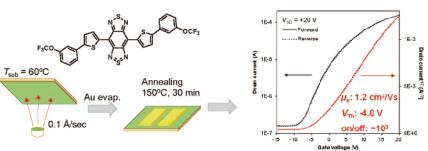
## High Mobility n-Type Organic Semiconductors TU-1, TU-3

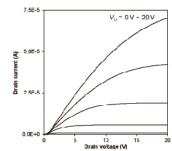
Advantages · Electron mobility >1 cm<sup>2</sup>/Vs

· Applicable to dry and/or wet processes

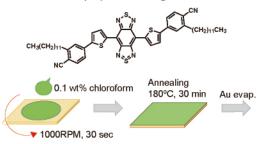
#### Performance evaluation of TU-1 and TU-3

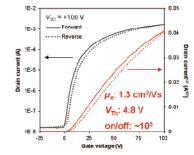
TU-1 [T3922]-based device (fabricated by vacuum deposition method)

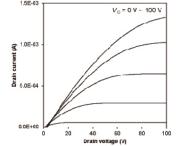




TU-3 [T3924]-based device (fabricated by spin coating method)







Previous research examples: 1) M. Mamada *et al., Chem. Mater.* **2015**, *27*, 141. DOI: https://doi.org/10.1021/cm503579m 2) Y. Takeda *et al., Sci. Rep.* **2016**, *6*, 25714. DOI: https://doi.org/10.1038/srep25714

TCI has evaluated and ensured semiconductor performance of OFET devices using our in-house equipment.

TU-1 and TU-3 are commercialized with the cooperation and help from Future Ink Corporation

#### **Quality assurance by OFET mobility**

TU-1 [**T3922**]

Electron mobility: >0.50 cm²/Vs (specification)

(SiO<sub>2</sub> / ODTS substrate)

TU-3 [**T3924**]

Electron mobility: >0.50 cm<sup>2</sup>/Vs (specification)

(SiO<sub>2</sub> / cPVP substrate)

#### **OFET characteristics of the TU-1, TU-3-based devices**

compound	Insulator	$V_{\text{\tiny SD}}[V]$	$\mu_{\text{\tiny avg}}$ .[cm²/Vs]	$\mu_{\text{max}}$ [cm²/Vs]	$V_{\text{Th}}[V]$	on/off
	SiO <sub>2</sub>	20	0.31 (0.01)	0.33	6.5 (0.2)	~106
TU-1 (vacuum deposition)	SiO <sub>2</sub>	40	0.45 (0.01)	0.46	9.6 (0.1)	~107
, , ,	SiO <sub>2</sub> / ODTS	20	0.88 (0.18)	1.18	-1.1 (2.6)	~10³
	SiO <sub>2</sub>	20	0.21 (0.03)	0.26	11.9 (0.4)	~105
TU-3 (spin coating)	SiO <sub>2</sub> / cPVP	20	0.51 (0.03)	0.55	5.0 (0.1)	~10³
	SiO <sub>2</sub> / cPVP	100	1.03 (0.14)	1.25	5.3 (1.3)	~105

The values in parentheses are standard deviations., cPVP: cross-linked polyvinylphenol

TU-1 and TU-3 have product specifications for the electron mobilities (>0.50 cm<sup>2</sup>/Vs) on OFET devices.

#### **Related Products**

High-quality p-type organic semiconductor

**Ph-BTBT-10** 100mg/250mg/1g [**D5491**]

Surface treatment agents

Octadecyltrichlorosilane (=ODTS) (>99.0%)

*n*-Octyltrichlorosilane (=OTS) 25g / 250g [O0168]

**1,1,1,3,3,3-Hexamethyldisilazane (=HMDS)** 25mL/100mL/500mL [H0089]

#### **High Performance S-shaped Organic Semiconductor** S-DNTT-10

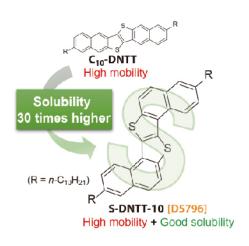
#### S-DNTT-10 [for organic electronics]

100mg / 250mg

#### [D5796]

- Advantages · High hole mobility > 10 cm<sup>2</sup>/Vs (Dip-coating method)
  - · Applicable to both dry and wet processes
  - High durability

#### **Device Characteristics**



#### **Performance of Dip-Coated OFETs** Based on S-DNTT-10 [D5796]

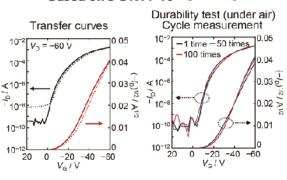


Table 1. Characteristics of OFETs based on **S-DNTT-10** [D5796]

Fabrication method	Surface modification Si/SiO₂ substrate	Maximum mobility (cm²/Vs)	Threshold voltage (V)	on/off
Wet (Dip-coating)	w/o (bare)	11	-17	107
Vacuum deposition	w/o (bare)	3.5	-8	107

Y. Yamaguchi, Y. Kojiguchi, S. Kawata, T. Mori, K. Okamoto, M. Tsutsui, T. Koganezawa, H. Katagiri, T. Yasuda, Chem. Mater. 2020, 32, 5350-5360. DOI: https://doi.org/10.1021/acs.chemmater.0c01740

#### **Characteristics**

R = 
$$-(CH_2)_3CH_3$$
 (n = 4)  
R =  $-(CH_2)_5CH_3$  (n = 6)  
R =  $-(CH_2)_7CH_3$  (n = 8)  
R =  $-(CH_2)_7CH_3$  (n = 10)  
(n = 4, 6, 8, 10)

Table 2. Physical property data<sup>1)</sup>

Compound	Solubilitya	НОМО	Mobility (cm²/Vs)		
Compound	(mmol/L)	(eV)	Vacuum deposition <sup>b</sup>	Wet process	
S-DNTT-4	19.4	-5.3	0.16	3.5 <sup>c</sup>	
S-DNTT-6	9.7	-5.3	$1.6 \times 10^{-3}$	6.8 <sup>c</sup>	
S-DNTT-8	8.0	-5.3	2.7	5.7 <sup>c</sup>	
S-DNTT-10 [D5796]	3.7	-5.3	3.5	11 <sup>c</sup>	
C10-DNTT <sup>2)</sup>	~0.12 <sup>2)</sup>	~4.93)	3.7 <sup>2)</sup>	11 <sup>4)</sup>	

<sup>&</sup>lt;sup>a</sup>Data obtained in toluene at 60 °C. <sup>b</sup>Data obtained using Si/SiO<sub>2</sub> (bare) substrates. <sup>c</sup>Dip-coating method.

#### References

- 1) Y. Yamaguchi, Y. Kojiguchi, S. Kawata, T. Mori, K. Okamoto, M. Tsutsui, T. Koganezawa, H. Katagiri, T. Yasuda, *Chem. Mater.* **2020**, *32*, 5350–5360.
- 2) M. J. Kang, I. Doi, H. Mori, E. Miyazaki, K. Takimiya, M. Ikeda, H. Kuwabara, *Adv. Mater.* **2011**, *23*, 1222–1225.
- 3) K.Takimiya, I. Osaka, T. Mori, M. Nakano, Acc. Chem. Res. 2014, 47, 1493–1502.
- 4) K. Nakayama, Y. Hirose, J. Soeda, M. Yoshizumi, T. Uemura, M. Uno, W. Li, N. J. Kang, M. Yamagishi, Y. Okada, E. Miyazaki, Y. Nakazawa, A.Nakao, K. Takimiya, J. Takeya, Adv. Mater. 2011, 23, 1626–1629.

DNTT-10 has a product specification for the hole mobility of > 3.0 cm<sup>2</sup>/Vs (vacuum deposition method, bare substrate) on OFET devices.

#### **Related Products**

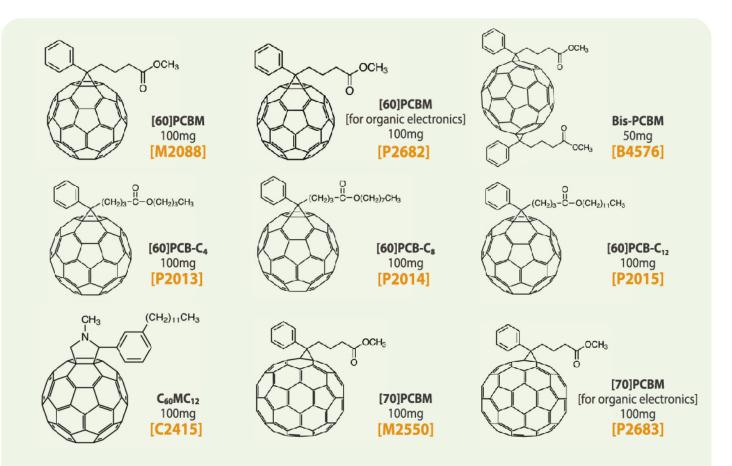
High-performance p-type organic semiconductor

Ph-BTBT-10 [for organic electronics] 100mg / 250mg [D5491]

High-performance n-type organic semiconductor

**TU-1** [for organic electronics] 100mg / 250mg [T3922] **TU-3** [for organic electronics] 100mg / 250mg [T3924]

### n-Type Organic Semiconductors Soluble Fullerene Derivatives



In comparison with traditional n-type organic semiconductor materials, these fullerene derivatives have high solubility in organic solvents and exhibit excellent basic properties.

They are used as coatable materials for organic electronics research.

#### References

#### **Organic Photovoltaic Cell (OPV)**

[M2088] Appl. Phys. Lett. 2001, 79, 2996; Nat. Mater. 2005, 4, 864.

[P2013] Solar Ener. Mater. Solar Cells, 2008, 92, 397; J. Phys. Chem. B, 2004, 108, 11921.

[P2014] Solar Ener. Mater. Solar Cells, 2010, 94, 537; J. Phys. Chem. B, 2004, 108, 11921.

[P2015] Synth. Metals 2003, 135, 827; J. Phys. Chem. B, 2004, 108, 11921.

#### **Organic Field-Effect Transistor (OFET)**

[M2088] Appl. Phys. Lett. 2004, 85, 4205; Synth. Metals. 2008, 158, 468.

[C 2415] Appl. Phys. Express 2010, 3, 101601; Appl. Phys. Lett. 2005, 87, 203504

#### **Organic Light-Emitting Diode (OLED)**

[M2088] J. Phys. Chem. C, 2009, 113, 14500; Macromolecules, 2006, 39, 177.

## Highly-purified n-Type Organic Semiconductor F<sub>16</sub>CuPc

F<sub>16</sub>CuPc (purified by sublimation) 100mg / 1g

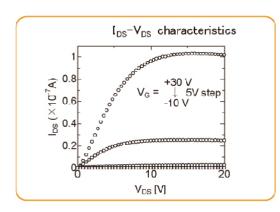
[H1194]

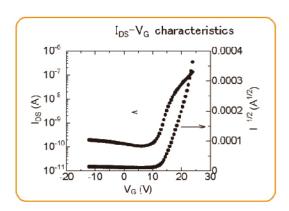
TCI's unique purification technology produces highly-purified semiconducting materials. We will ensure a stable supply of "F<sub>16</sub>CuPc" being used as an organic semiconductor with high electron mobility.



#### **Transistor Characteristics**

The FET device made using our F<sub>16</sub>CuPc as an n-type semiconductor shows good characteristics.





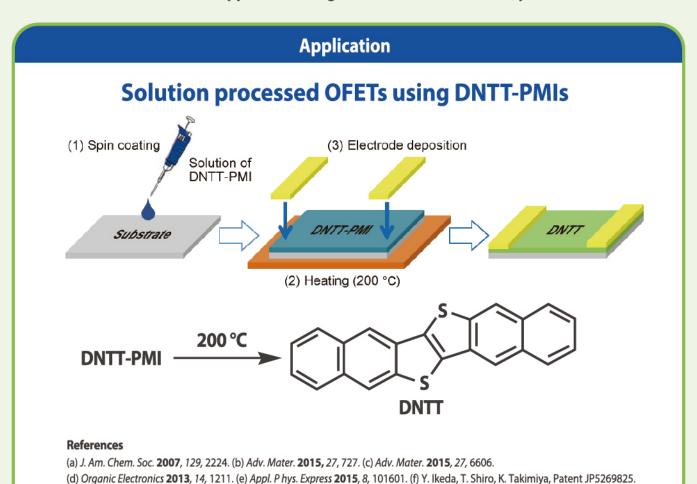
The characteristics above are presented by Dr. Yasuyuki Watanabe.

#### **Related Products**

F<sub>8</sub>CuPc (purified by sublimation)100mg / 1g[C2427]Pentacene (99.999%, trace metals basis) (purified by sublimation)100mg / 1g[P2524]DPh-BTBT (purified by sublimation)100mg[D3526]Ph-BTBT-10100mg / 250mg / 1g[D5491]

#### **Organic Transistor Reagent Soluble DNTT Precursor**

- **Advantages** · Solution-processable DNTT precursor
  - · Thermally convertible to DNTT in thin-film
  - Applicable to organic transistor and memory devices



These product was commercialized with the cooperation of TEIJIN LIMITED.

#### **Measurement of OFETs fabricated by using DNTT-PMI**

#### **Device fabrication (endo-DNTT-PMI)**

- (1) Mix endo-DNTT-PMI and polystyrene in 2:1 weight ratio
- (2) Dissolve mixed powder in CHCl<sub>3</sub> to prepare 1wt% solution
- (3) Spin-coat the solution onto cleaned- and  $UV/O_3$  treated-  $n^+$ -Si/SiO<sub>2</sub> substrate
- (4) Anneal substrates at 200 °C for 10 min under air for converting the precursor to DNTT thin film
- (5) Fabricate source and drain electrodes by vacuum deposition of Au

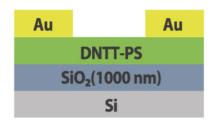


Figure 1. Device structure

#### **Thin-film and OFET properties**

Figure 2 shows polarized optical microscopy (POM) image of DNTT thin film prepared from DNTT-PMI. Image clearly shows polycrystalline film morphology. As shown in Figure 3, fabricated devices show typical p-type characteristics.

Maximum carrier mobility 0.86 cm²/Vs was observed when channel length was 200  $\mu$ m. Carrier mobility was greatly improved to 2.33 cm²/Vs when the channel length was shortened to 20  $\mu$ m. This high mobility can be assumed to be as following: the source and drain channels were completely filled in single grain, so the carrier transportation barrier caused by grain boundaries reduced.

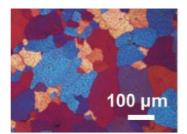
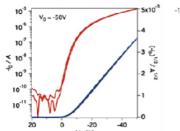


Figure 2. POM image of DNTT thin film.



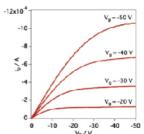


Figure 3. Transfer (left) and output (right) curves of OFET device prepared from endo-DNTT-PMI.

Device	Anneal. Temp. (°C)	Channel Length (µm)	Mobility (cm²/Vs)	on/off	V <sub>th</sub> (V)
1	200	200	0.86	4.8 × 10'	-5.5
2	210	200	0.85	4.6 × 10 <sup>5</sup>	-0.9
3	210	20	2.33	1.1 × 10	-3.1

Table 1. Summary of OFET properties of DNTT prepared from endo-DNTT-PMI.

#### Other notices of DNTT-PMIs

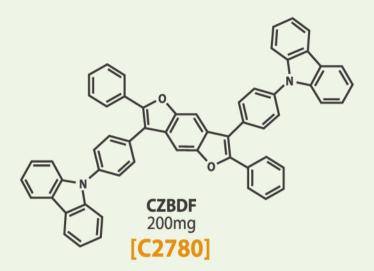
Solubility: exo-DNTT-PMI [D5154] (0.2wt% in CHCl<sub>3</sub>)

Condition to Store: Store in the dark because the color of exo-DNTT-PMI gradually turns to redu under

light irradiation

## **Ambipolar Organic Semiconductor : CZBDF**

-Organic material with well-balanced high hole and electron mobility-

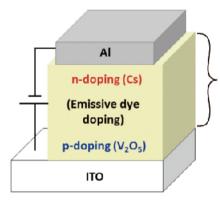


#### Advantages

- · Well-balanced high hole and electron
- mobility (Hole:  $3.7 \times 10^{-3}$  cm<sup>2</sup>/Vs,
- Electron: 4.4 × 10<sup>-3</sup> cm<sup>2</sup>/Vs;
   Amorphous, TOF technique)
- High glass-transition temperature (T<sub>g</sub> = 162 °C)
- · Wide band gap (3.3 eV)
- Serves as a host material for fluorescent and red phosphorescent dopants.

#### **Application**

#### **Host material for homojunction OLED**



Single matrix of CZBDF

EQE: up to 4.2% (C545T as an emission dopant)

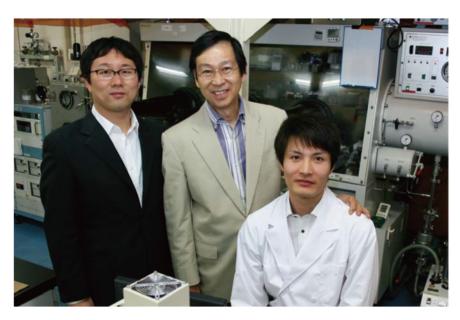
Reference H. Tsuji, C. Mitsui, Y. Sato, E. Nakamura, Adv. Mater. 2009, 21, 3776. DOI: https://doi.org/10.1002/adma.200900634

#### **Related Products**

Coumarin 545T (= C545T)	200mg	[B4257]
2,5,8,11-Tetra-tert-butylperylene (= TBP)	100mg	[T3053]
Rubrene (purified by sublimation)	250mg / 1g	[T2233]
Ir(piq)₃ (purified by sublimation)	100mg	[T2685]
Alq₃ (purified by sublimation)	5g	[T2238]
$N,N'$ -Di-1-naphthyl- $N,N'$ -diphenylbenzidine (= $\alpha$ -NPD) (purified by sublimation)	1g/5g	[D3970]

#### Introduction of the researcher

#### Physical Organic Chemistry Laboratory (Nakamura Group), Department of Chemistry, University of Tokyo

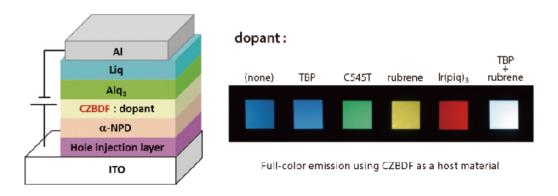


From left: Associate Prof. Dr. Hayato Tsuji, Prof. Dr. Eiichi Nakamura, Dr. Chikahiko Mitsui

#### Contents of the research

The Nakamura group has pioneered organic chemistry spreading to various research fields based on their manufacturing by synthetic organic chemistry. Their studies involve development of a C-H activation reaction using an iron catalyst, organic electronics materials useful for organic solar cells, organic light-emitting diodes (OLED) and molecular transistors as well. They also research on a novel cure method by introducing a gene. Recently, their study on an electron microscope enabled us to directly observe various motions and crystal growths of individual molecules.

#### Host material for heterojunction OLED



Reference C. Mitsui, H. Tsuji, Y. Sato, E. Nakamura, Chem. Asian J. 2012, 7, 1443. DOI: https://doi.org/10.1002/asia.201200062

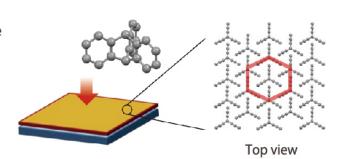
## Triptycene-type SurfaceTreatment Agent for Completely Orientated Molecular Film

#### Advantages

- Forms completely oriented molecular thin films on any substrate layer.
- Applicable to dry and wet processes
- Enables the improvement of OFET performance by inserting its film under an active layer

#### Self-assembly of Triptycene on a substrate 1-4)

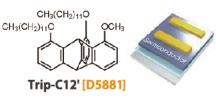
A propeller-shaped molecular structure consisting of three phenylene rings



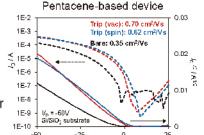
Side view

Forming of a 2D nested hexagonal packing sheet and 1D layer stacking structure

#### Surface Modification using Trip-C12' for the Improvement of OFET Performance



deposited by vacuum-evaporation or spin-coating on Si/SiO<sub>2</sub> substrate.



Fullurene C<sub>60</sub>-based device

1E-4

1E-5

Trip (vac): 0.062 cm²/Vs

Trip (spin): 0.056 cm²/Vs

Bare: 0.039 cm²/Vs

1E-7

1E-8

1E-9

1E-10

1E-11

1E-11

1E-11

1E-11

1E-10

1E-11

1E-10

1E-11

1E-10

1E-11

1E-10

1E

The OFET mobilities increased by inserting the Trip-C12' layers

This product is commercialized under the license agreement based on the patents (No. JP6219314B2 and No. JP6272242B2) invented by Prof. Takanori Fukushima.

#### Film deposition procedure of Trip-C12'

Deposition method	Vacuum-evaporation <sup>2)</sup>	Blade-coating <sup>3)</sup>	Spin-coating <sup>1)</sup>
Substrate, Insulator	SiO₂, AlOҳ, Polyimide, Parylene	Parylene	Silicon wafer
Deposition condition	Thickness : 5nm Without substrate heating during deposition	0.5mM Mesitylene solution Blade speed : 40~50 μm/sec Substrate temperature : 50~60°C	5mM Toluene solution Rotation speed : 2000RPM
Annealing	120°C, 1 hour, N₂	120°C, 1 hour, vacuum (~100Pa)	120°C, 1 hour

#### References

- 1) N. Seiki, Y. Shoji, T. Kajitani, F. Ishiwari A. Kosaka T. Hikima, M. Takata, T. Someya, T. Fukushima, *Science* **2015**, *348*, 1122. DOI: https://doi.org/10.1126/science.aab1391
- 2) T. Yokota, T. Kajitani, R. Shidachi, T. Tokuhara, M. Kaltenbrunner, Y. Shoji, F. Ishiwari, T. Sekitani, T. Fukushima, T. Someya, *Nat. Nanotechnol.* **2018**, *13*, 139.
  - DOI: https://doi.org/10.1038/s41565-017-0018-6
- 3) M. Kondo, T. Kajitani, T. Uemura, Y. Noda, F. Ishiwari, Y. Shoji, T. Araki, S. Yoshimoto, T. Fukushima, T. Sekitani, *Sci. Rep.* **2019**, *9*, 9200. DOI: https://doi.org/10.1038/s41598-019-45559-4
- 4) M. Kondo, T. Uemura, F. Ishiwari, T. Kajitani, Y. Shoji, M. Morita, N. Namba, Y. Inoue, Y. Noda, T. Araki, T. Fukushima, T. Sekitani, *ACS Appl. Mater. Interface* **2019**, *11*, 41561.
  - DOI: https://doi.org/10.1021/acsami.9b13056

#### **Related Products**

#### Trip-C12' precursor

1,8,13-Trihydroxytriptycene

**High-quality organic semiconductors** 

Pentacene	100mg/1g	[P2524]
Fullerene C <sub>60</sub>	100mg	[F1232]
Ph-BTBT-10	100mg/250mg/1g	[D5491]
S-DNTT-10	100mg / 250mg	[D5796]
TU-1 [for organic electronics]	100mg / 250mg	[T3922]
TU-3 [for organic electronics]	100mg / 250mg	[T3924]

500mg [**D5823**]

#### **Surface treatment agent**

Trichlorooctadecylsilane (>99.0%) 1g [T3815]

memo

## Details of Representative TCI's Products

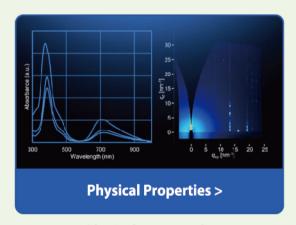
#### Organic Transistor

TCI has begun in-house fabrication and assessment of organic transistors by using our products. The results of device performance and its functionality provide us the feedback on synthesis and its purification processes to improve our technology and skill. This helps us to provide more reliable reagents to our customers. In addition, we also release several useful physical properties of our products (e.g. UV-Vis spectra and 2D-GIXD data).





Details of device fabrication methods and device characteristics.

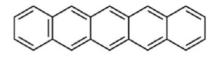


Physical property data (e.g. UV-Vis spectra and 2D-GIXD).





#### Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): Pentacene



Pentacene (99.999%, trace metals basis) (purified by sublimation)

CAS RN: 135-48-8

Product Number: P2524

#### Performance of Pentacene [P2524]-based OFETs



Vacuum Deposition Method

Organic Semiconductor
Insulator
Gate

Top-Contact Bottom-Gate Type (TCBG)

Table. OFETs Characteristics of Pentacene [P2524]-based OFETs

Entry	Fabrication Method	Device Configuration	SAM Treatment	T <sub>sub</sub> (°C)	Polarity	$\mu$ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Vacuum deposition	TCBG	w/o Bare	RT	р	0.33	-15	10 <sup>5</sup>
2	Vacuum deposition	TCBG	OTS	RT	р	1.2	-7.0	10 <sup>6</sup>

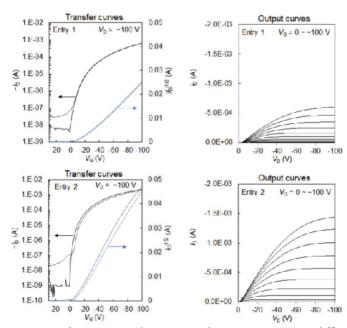


Figure. Transfer curves in the saturated region and output curves at different gate voltages

#### **Experimental details**

Fabrication and evaluation of vacuum-deposited Pentacene [P2524]-based OFETs

#### < Substrate >

- Bare Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)
- OTS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)

#### < Self-Assembly Monolayer (SAM) Treatment >

- n-Octyltrichlorosilane (OTS) [00168]
- 1. Piranha etching (H<sub>2</sub>SO<sub>4</sub>:H<sub>2</sub>O<sub>2</sub>=4:1, 80°C, 2h)
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3min)
- 4. UV/O<sub>3</sub> treatment (1h)
- 5. Immersion in OTS solution (0.01 M toluene, 16h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

#### < Vacuum Deposition >

- Deposition rate of Pentacene [P2524] : 0.1 Å/s (under a pressure of  $\sim 10^{-5}$  Pa)
- Substrate temperature during deposition: RT
- Deposition rate of Au : 0.3 Å/s, (under a pressure of  $\sim 10^{-4}$  Pa)

#### < Device Configuration >

- [n<sup>+</sup>-Si/SiO<sub>2</sub> (200 nm) / Pentacene [P2524] (60 nm) / Au (60 nm)]
- Top-Contact Bottom-Gate Type (TCBG)
- Channel Length: 50 µm
- · Channel width: 1.5 mm: 1.5 mm

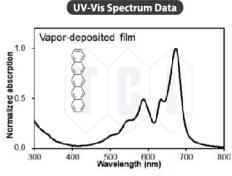
#### < Evaluation Condition >

- Under N<sub>2</sub>
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation:  $I_D = (W/2L) \mu Ci (V_G V_{th})^2$

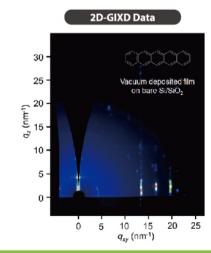
#### TCI products used in this experiment

[P2524] Pentacene (99.999%, trace metals basis) (purified by sublimation)

[O0168] n-Octyltrichlorosilane (OTS)



λ<sub>peak</sub>(nm): 673, λ<sub>edge</sub>(nm): 699



#### Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): TIPS Pentacene

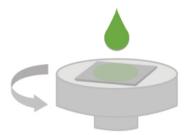
$$\begin{array}{c|c} CH_3 & CH_3 \\ CH_3 & CH_3 \\ CH_3 & CH_3 \\ CH_3 & CH_3 \\ \end{array}$$

### 6,13-Bis(triisopropylsilylethynyl)pentacene (This product is unavailable in the U.S.) [for organic electronics]

TIPS Pentacene

CAS RN: 373596-08-8 Product Number: **B5942** 

#### Performance of TIPS Pentacene [B5942]-based OFETs



Spin-Coating Method

Organic Semiconductor					
Source		Drain			
Insulator					
	Gate				

Bottom-Contact Bottom-Gate Type (BCBG)

#### Table. OFETs Characteristics of TIPS Pentacene [B5942]-based OFETs

Entry	Fabrication Method	Device Configuration	SAM Treatment	Polarity	μ (cm² V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Spin-coating	BCBG	HMDS (SiO <sub>2</sub> ) PFBT (Au)	р	0.12	-1.2	10 <sup>5</sup>

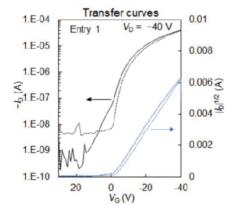


Figure. Transfer curves in the saturated region

Fabrication and evaluation of vacuum-deposited TIPS Pentacene [B5942]-based OFETs

#### < Substrate >

• HMDS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm) + with PFBT-treated Au electrodes (thickness of Au : 40 nm)

#### < Vacuum Deposition >

• Deposition rate of Au : 0.2 Å/s, (under a pressure of  $\sim 10^{-4}$  Pa)

#### < Vacuum Deposition >

- PFBT [P0861] (For Au surface treatment) + HMDS [H0089] (For Si/SiO<sub>2</sub> surface treatment)
- 1. UV/O<sub>3</sub> treatment (20 min)
- 2. Immersion in PFBT [P0861] solution (0.01 M toluene, 3 min, Air)
- 3. Exposure to vapor (IPA, 1 min)
- 4. Spin-coating of HMDS [H0089] (4000 RPM, 40 sec, Air)
- 5. Exposure to vapor (IPA, 1 min)

#### < Spin-coating >

- TIPS Pentacene [B5942], 1 mg/mL toluene
- Spin-coating condition: 1000 RPM, 60sec, N2

#### < Device configuration >

- [n<sup>+</sup>-Si/SiO<sub>2</sub> (200 nm) / Au (40 nm) / TIPS Pentacene [**B5942**] (15 nm) ]
- Bottom-Contact Bottom-Gate Type (BCBG)
- Channel Length: 50 µm
- Channel width: 1.5 mm

#### < Evaluation condition >

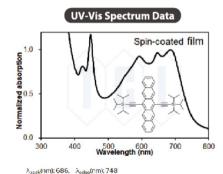
- Under N₂
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation :  $I_D = (W/2L) \mu Ci (V_G V_{th})^2$

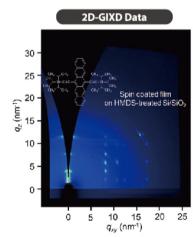
#### TCI products used in this experiment

[B5942] 6,13-Bis(triisopropylsilylethynyl)pentacene (This product is unavailable in the U.S.) [for organic electronics]

[P0861] Pentafluorobenzenethiol

[H0089] 1,1,1,3,3,3-Hexamethyldisilazane





## Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): P3HT

 $\begin{array}{c|c} & \text{(CH}_2)_5\text{CH}_3 \\ \hline \\ & \text{S} \end{array}$ 

#### Poly(3-hexylthiophene-2,5-diyl) (regioregular)

P3HT

CAS RN: 125321-66-6 Product Number: **P2513** 

#### Performance of P3HT (regionegular) [P2513]-based OFETs



Spin-Coating Method

Source	Drain					
Organic Semiconductor						
Insulate	or					
Gate						

Top-Contact Bottom-Gate Type (TCBG)

Table. OFETs Characteristics of P3HT (regionegular) [P2513]

Entry	Fabrication Method	Device Configuration	SAM Treatment	Annealing Temp. <sup>a</sup> (°C)	Polarity	μ (cm² V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Spin-coating	TCBG	OTS	100	р	0.12	9.9	10 <sup>3</sup>

<sup>&</sup>lt;sup>a</sup>Post-annealing temperature.

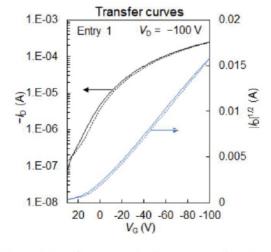


Figure. Transfer curves in the saturated region

Fabrication and evaluation of spin-coated P3HT (regionegular) [P2513]-based OFETs

#### < Substrate >

• OTS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 300 nm)

#### < Self-Assembly Monolayer (SAM) Treatment >

- n-Octyltrichlorosilane (OTS) [00168]
- 1. Piranha etching (H<sub>2</sub>SO<sub>4</sub>:H<sub>2</sub>O<sub>2</sub>=4:1, 80°C, 2h)
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3 min)
- 4. UV/O<sub>3</sub> treatment (1 h)
- 5. Immersion in OTS solution (0.01 M toluene, 16 h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

#### < Spin-Coating >

- P3HT (regioregular) [P2513] 10 mg/mL, 1,2,4-Trichlorobenzene: Chloroform (2:98) mixed solvent
- Spin-coating condition: 1500 RPM, 60 sec, N<sub>2</sub>

#### < Vacuum Deposition >

• Deposition rate of Au : 0.2 Å/s (under a pressure of  $\sim 10^{-4}$  Pa)

#### < Post-Annealing Treatment >

• Annealing condition: 100 °C, 30 min, N<sub>2</sub>

#### < Device Configuration >

• [n<sup>+</sup>-Si/SiO<sub>2</sub> (300 nm) / P3HT (regioregular) [P2513] (100 nm) / Au (40 nm)]

Bottom-Contact Bottom-Gate Type (TCBG)

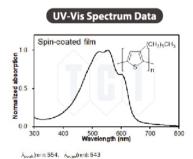
Channel Length :  $50 \mu m$ Channel width : 1.5 mm

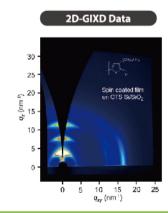
#### < Evaluation Condition >

- Under N<sub>2</sub>
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation :  $I_D = (W/2L) \mu Ci (V_G V_{th})^2$

#### TCI products used in this experiment

[P2513] Poly(3-hexylthiophene-2,5-diyl) (regioregular) [O0168] *n*-Octyltrichlorosilane (OTS)





# Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): Fullerene C70



# Fullerene C70 (purified by sublimation) [for organic electronics]

Fullerene C70

CAS RN: 115383-22-7

Product Number: F1233

#### Performances of C70 [F1233]-based OFETs



Vacuum Deposition Method

Source Drain

Organic Semiconductor

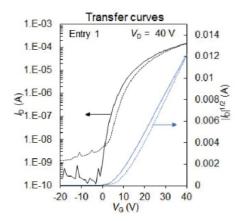
Insulator

Gate

Top-Contact Bottom-Gate Type (TCBG)

Table. OFETs Characteristics of Fullerene C70 [F1233]-based OFETs

Entry	Fabrication Method	Device Configuration	SAM Treatment	T <sub>sub</sub> (°C)	Polarity	$\mu$ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Vacuum deposition	TCBG	HMDS	RT	n	0.52	6.7	10 <sup>6</sup>
2	Vacuum deposition	TCBG	OTS	RT	n	0.55	8.3	10 <sup>6</sup>



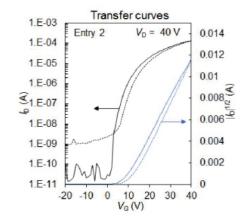


Figure. Transfer curves in the saturated region

Fabrication and evaluation of vacuum-deposited Fullerene C70 [F1233]-based OFETs

#### < Substrate >

- HMDS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)
- OTS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)

#### < Self-Assembly Monolayer (SAM) Treatment >

- 1,1,1,3,3,3-Hexamethyldisilazane (HMDS) [H0089] n-Octyltrichlorosilane (OTS) [O0168]
- 1. Piranha etching (H<sub>2</sub>SO<sub>4</sub>:H<sub>2</sub>O<sub>2</sub>=4:1, 80°C, 2h)
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3 min)
- 4. UV/O<sub>3</sub> treatment (1 h)
- 5. Immersion in HMDS (16 h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

- 1. Piranha etching  $(H_2SO_4:H_2O_2=4:1, 80^{\circ}C, 2h)$
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3 min)
- 4. UV/O<sub>3</sub> treatment (1 h)
- 5. Immersion in OTS solution (0.01 M toluene, 16 h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

#### < Vacuum Deposition >

- Deposition rate of C70 [F1233] 0.2 Å/s (under a pressure of  $\sim 10^{-5}$  Pa)
- Substrate temperature during deposition: RT
- Deposition rate of Au : 0.2 Å/s (under a pressure of  $\sim 10^{-5} \text{ Pa}$ )

#### < Device configuration >

- [n+-Si/SiO<sub>2</sub> (200 nm) / C70 [F1233] (40 nm) / Au (40 nm)]
- Top-Contact Bottom-Gate Type (TCBG)
- Channel Length: 50 µm
- · Channel width: 1.5 mm

#### < Evaluation condition >

- Under N<sub>2</sub>
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation :  $I_D = (W/2L) \mu Ci (V_G - Vth)^2$

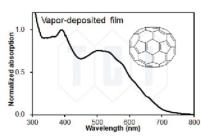
#### TCI products used in this experiment

[F1233] Fullerene C70 (purified by sublimation) [for organic electronics]

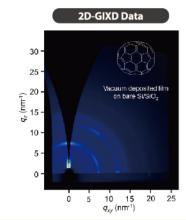
[H0089] 1,1,1,3,3,3-Hexamethyldisilazane (HMDS)

[O0168] n-Octyltrichlorosilane (OTS)

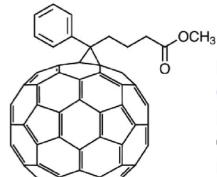
#### UV-Vis Spectrum Data



 $\lambda_{\text{peak}}$ (nm): 390,  $\lambda_{\text{edge}}$ (nm): 715



## Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): [70]PCBM

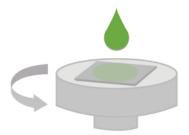


[6,6]-Phenyl-C71-butyric Acid Methyl Ester (mixture of isomers)[for organic electronics]

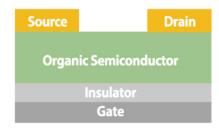
[70]PCBM (mixture of isomers)

CAS RN: 609771-63-3 Product Number: **P2683** 

#### Performance of [70]PCBM[P2683]-based OFETs



Spin-Coating Method



Top-Contact Bottom-Gate Type (TCBG)

Table. OFETs Characteristics of [70]PCBM[P2683]-based OFETs

Entry	Fabrication Method	Device Configuration	SAM Treatment	Polarity	$\mu$ (cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Spin-coating	TCBG	HMDS	n	$2.5 \times 10^{-2}$	8.8	10 <sup>4</sup>

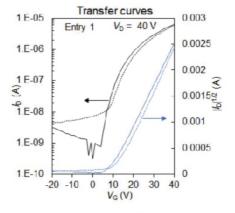


Figure. Transfer curves in the saturated region

Fabrication and evaluation of spin-coated [70]PCBM[P2683]-based OFETs

#### < Substrate >

HMDS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)

#### < Self-Assembly Monolayer (SAM) Treatment >

- 1,1,1,3,3,3-Hexamethyldisilazane (HMDS) [H0089]
- 1. Piranha etching (H<sub>2</sub>SO<sub>4</sub>:H<sub>2</sub>O<sub>2</sub>=4:1, 80°C, 2h)
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3 min)
- 4. UV/O<sub>3</sub> treatment (1 h)
- 5. Immersion in HMDS (16 h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

#### < Spin-Coating >

- [70]PCBM[P2683], 15 mg/mL, Chloroform
- Spin-coating condition: 2000 RPM, 60 sec, N2

#### < Vacuum Deposition >

• Deposition rate of Au : 0.2 Å/s (under a pressure of~10<sup>-4</sup>Pa)

#### < Device configuration >

- [n<sup>+</sup>-Si/SiO<sub>2</sub> (200 nm) / [70]PCBM[P2683] / Au (40 nm)]
- Top-Contact Bottom-Gate Type (TCBG)
- Channel Length : 50 μm
- Channel width: 1.5 mm

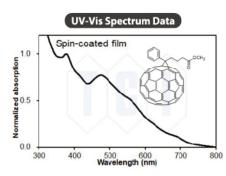
#### < Evaluation condition >

- Under N<sub>2</sub>
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation: $I_D = (W/2L) \mu Ci (V_G V_{th})^2$

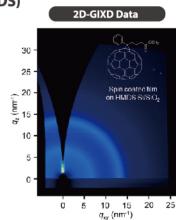
#### TCI products used in this experiment

[P2683] [70]PCBM (mixture of isomers)

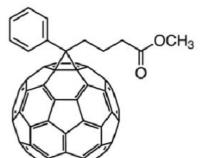
[H0089] 1,1,1,3,3,3-Hexamethyldisilazane (HMDS)







## Fabrication and Evaluation of Organic Field-Effect Transistors (OFETs): [60]PCBM

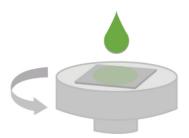


[6,6]-Phenyl-C61-butyric Acid Methyl Ester [for organic electronics]

[60]PCBM

CAS RN: 115383-22-7 Product Number: **P2682** 

#### Performance of [60]PCBM [P2682]-based OFETs



Spin-Coating Method

Source Drain

Organic Semiconductor

Insulator

Gate

Top-Contact Bottom-Gate Type (TCBG)

#### Table. OFETs Characteristics of [60]PCBM [P2682]-based OFETs

Entry	Fabrication Method	Device Configuration	SAM Treatment	T <sub>sub</sub> (°C)	Polarity	μ (cm² V <sup>-1</sup> s <sup>-1</sup> )	V <sub>th</sub> (V)	I <sub>on</sub> /I <sub>off</sub>
1	Spin-coating	TCBG	HMDS	RT	n	2.4 × 10 <sup>-2</sup>	6.7	10 <sup>4</sup>

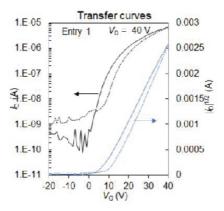


Figure. Transfer curves in the saturated region

Fabrication and evaluation of spin-coated [60]PCBM [P2682]-based OFETs

#### < Substrate >

HMDS-treated Si/SiO<sub>2</sub> (thickness of SiO<sub>2</sub>: 200 nm)

#### < Self-Assembly Monolayer (SAM) Treatment >

- 1,1,1,3,3,3-Hexamethyldisilazane (HMDS) [H0089]
- 1. Piranha etching (H<sub>2</sub>SO<sub>4</sub>:H<sub>2</sub>O<sub>2</sub>=4:1, 80°C, 2h)
- 2. Ultrasonication (Deionized water, Acetone, IPA, 10 min each)
- 3. Exposure to vapor (IPA, 3 min)
- 4. UV/O<sub>3</sub> treatment (1 h)
- 5. Immersion in HMDS (16 h, N<sub>2</sub>)
- 6. Ultrasonication (Toluene, Acetone, IPA, 10 min each)

#### < Spin-Coating >

- [60]PCBM [P2682], 15 mg/mL, Chloroform
- Spin-coating condition: 3000 RPM, 60 sec, N<sub>2</sub>

#### < Vacuum Deposition >

• Deposition rate of Au: 0.2 Å/s (under a pressure of~10-4 Pa)

#### < Device configuration >

- [n<sup>+</sup>-Si/SiO<sub>2</sub> (200 nm) / [60]PCBM [P2682] / Au (40 nm)]
- Top-Contact Bottom-Gate Type (TCBG)
- Channel Length: 50 μm
- · Channel width: 1.5 mm

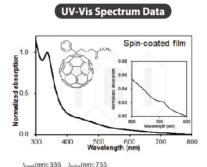
#### < Evaluation condition >

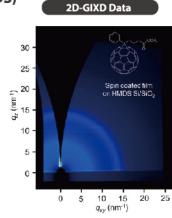
- Under N<sub>2</sub>
- Field-effect mobilities ( $\mu$ ) were determined from the transfer curves in the saturation regime using the following equation: $I_D = (W/2L) \mu Ci (V_G V_{th})^2$

#### TCI products used in this experiment

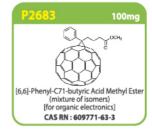
[P2682] [60]PCBM

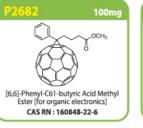
[H0089] 1,1,1,3,3,3-Hexamethyldisilazane (HMDS)

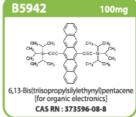


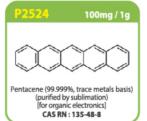


## High-Quality Organic Semiconductor Materials



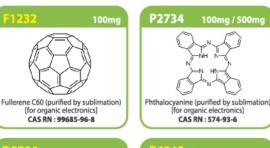




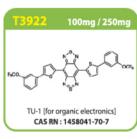


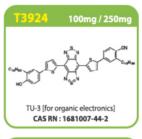


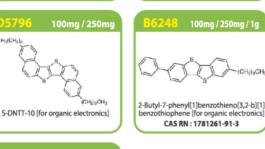


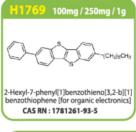


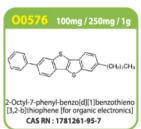


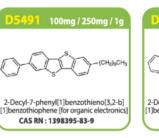


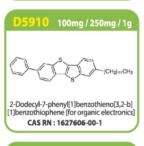




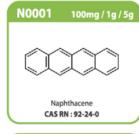


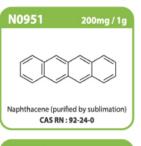


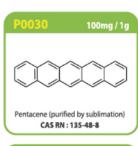


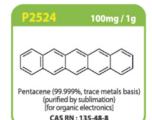


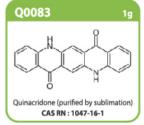


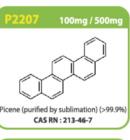


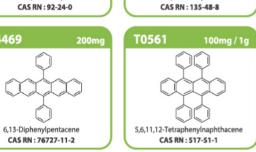




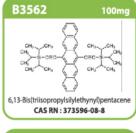


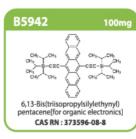




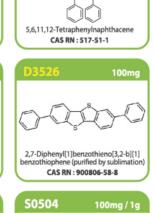


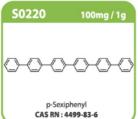


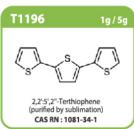


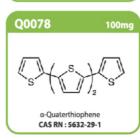


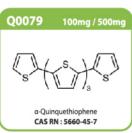


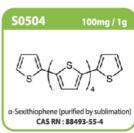


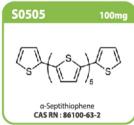


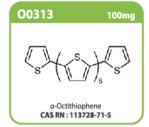


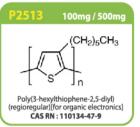


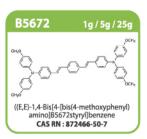


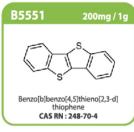






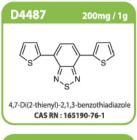


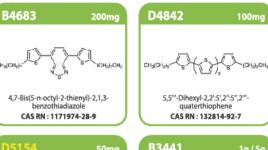


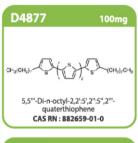




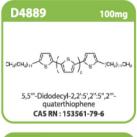


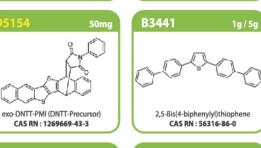




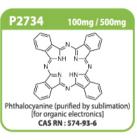




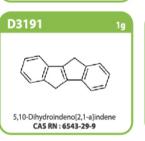


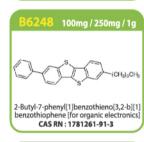


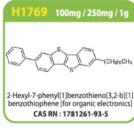


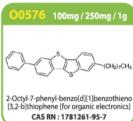


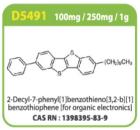


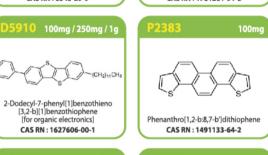


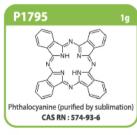






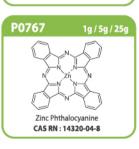


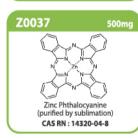


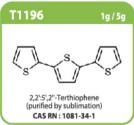




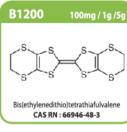








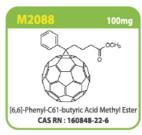


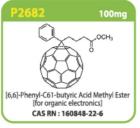


# n-Type Organic Semiconductors



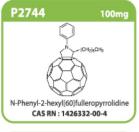












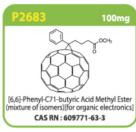




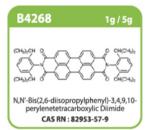


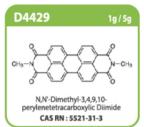


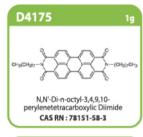


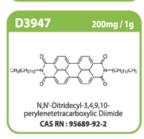


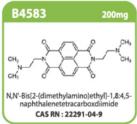


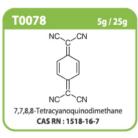


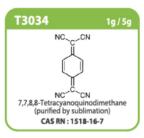


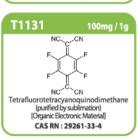


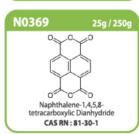


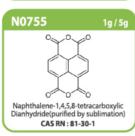




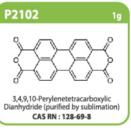


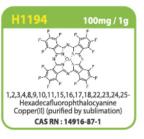


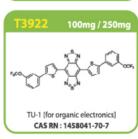


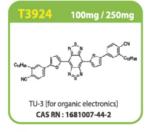




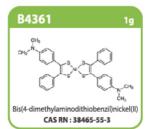












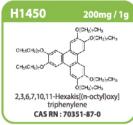


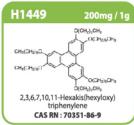


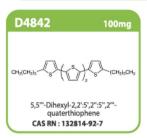
# **Liquid Crystalline Semiconductors**

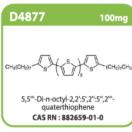
# B4683 200mg CH<sub>9</sub>(CH<sub>2</sub>), S N (CH<sub>2</sub>, CH<sub>3</sub> 4,7-Bis(5-n-octyl-2-thienyl)-2,1,3-benzothiadiazole

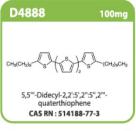
CAS RN: 1171974-28-9

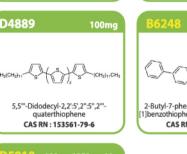


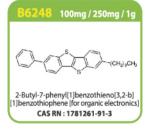


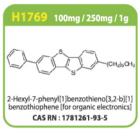


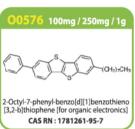




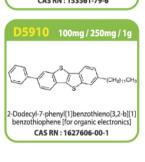




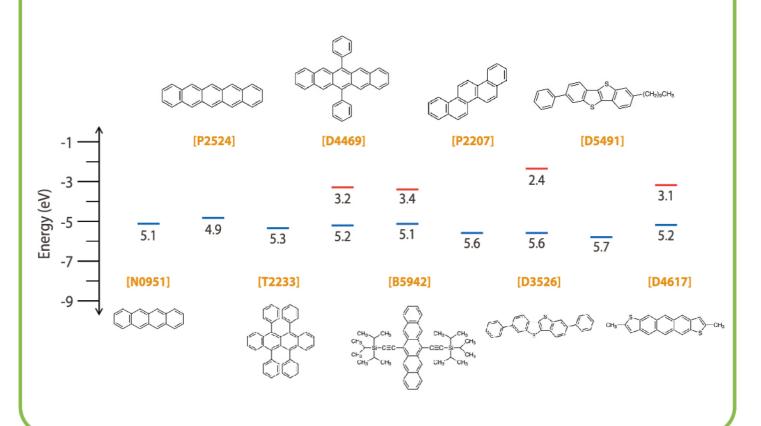




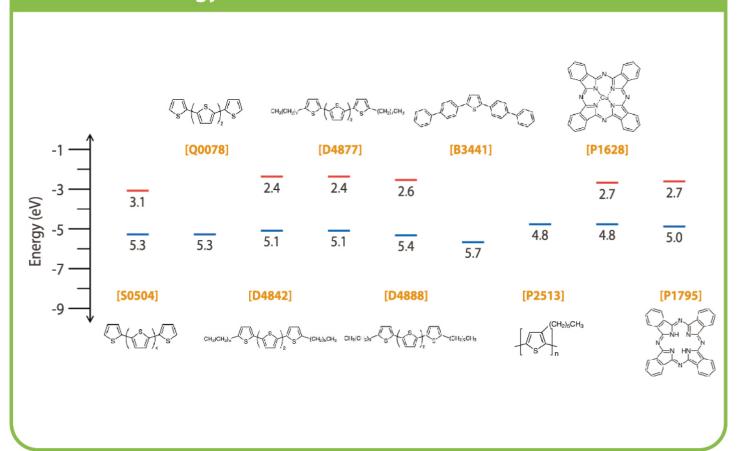




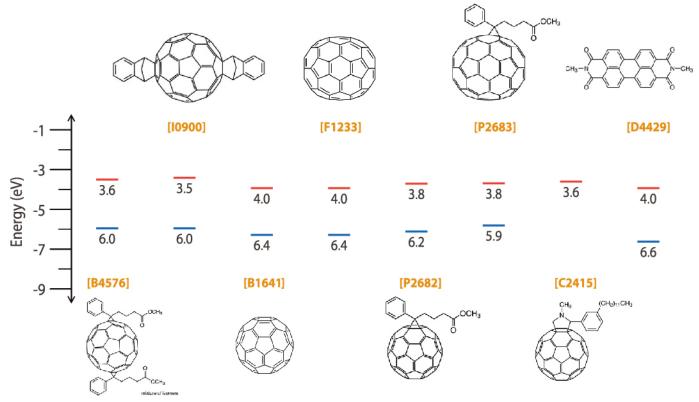
# **Energy level of materials (HOMO, LUMO)**



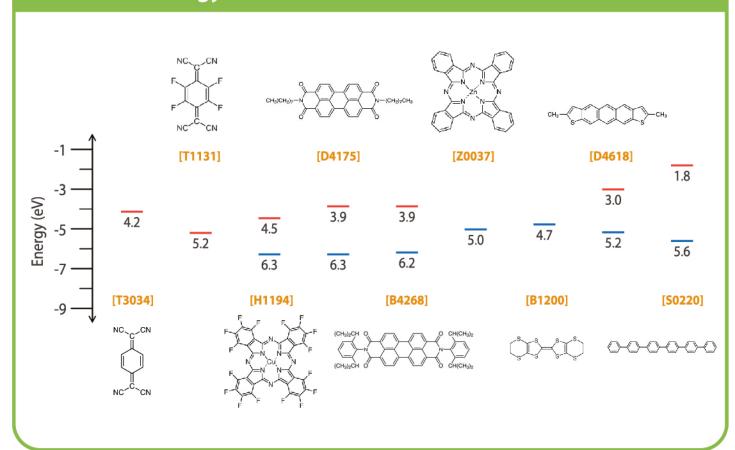
# **Energy level of materials (HOMO, LUMO)**



# Energy level of materials (HOMO, LUMO)



# **Energy level of materials (HOMO, LUMO)**





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